

ISSN 0022-3727

IoP

# Journal of Physics D Applied Physics

Volume 33 Number 11 7 June 2000

Review article: **Nanoassembled model catalysts**

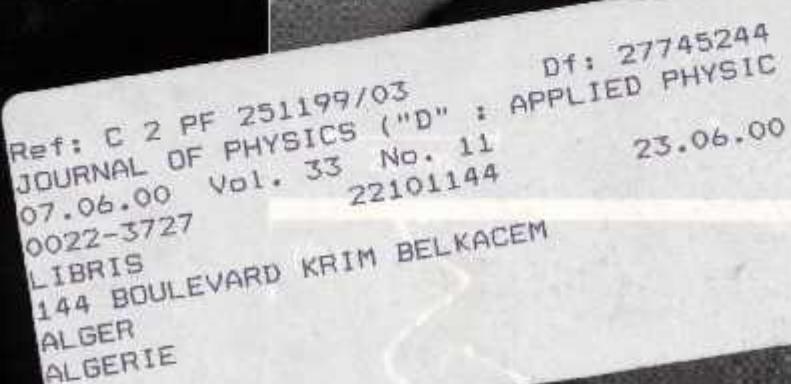
*U Heiz and W-D Schneider*

Online: [www.iop.org/Journals/jd](http://www.iop.org/Journals/jd)

A Journal Recognized by  
The European Physical Society



(a)



# Journal of Physics D: Applied Physics

Volume 33 Number 11 7 June 2000

## RAPID COMMUNICATION

- L65 Channel switching and magnetoresistance of a metal-SiO<sub>2</sub>-Si structure  
J Dai, L Spinu, K-Y Wang, L Malkinski and J Tang

## REVIEW ARTICLE

- R85 Nanoassembled model catalysts  
U Heiz and W-D Schneider

## PAPERS

### APPLIED INTERFACES AND SURFACES

- 1245 Dynamic Taylor cone formation on liquid metal surface: numerical modelling  
V G Suvorov and E A Litvinov
- 1252 Kinetic parameters of some tissue equivalent thermoluminescence materials  
G Kitis, C Furetta, M Prokic and V Prokic
- 1263 Synthesis and characterization of Y<sub>2</sub>O<sub>3</sub>:Eu<sup>3+</sup> thin films on silicon substrate by pulsed laser ablation  
G Gu, P P Ong, C Chen and S Roth

### APPLIED MAGNETISM AND MAGNETIC MATERIALS

- 1267 Magnetoresistance of metallic magnetic multilayers in the ballistic regime for a spacer  
V F Los and A N Pogorily

### ELECTROMAGNETISM, OPTICS, ACOUSTICS, HEAT TRANSFER, CLASSICAL MECHANICS AND FLUID DYNAMICS

- 1276 Plasma loaded helical waveguide  
B A Aničin
- 1282 Sealed-off CO<sub>2</sub> lasers excited by an all-solid-state 0.6 MHz generator  
S Wieneke, S Born and W Viöl
- 1287 Simultaneous generation of longitudinal and shear bulk ultrasonic waves in solids  
J M Rouvaien, A Menhaj-Rivenq, P Logette, P Goutin and F Haine

### PHYSICS OF GASES, PLASMAS AND ELECTRIC DISCHARGES

- 1298 Diffusion of electrons in time-dependent  $E(t) \times B(t)$  fields  
Z Raspopović, S Sakadžić, Z Lj Petrović and T Makabe
- 1303 Atomic oxygen recombination on fused silica: modelling and comparison to low-temperature experiments (300 K)  
G Cartry, L Magne and G Cernogora
- 1315 Time-resolved laser-induced fluorescence study of NO removal plasma technology in N<sub>2</sub>/NO mixtures  
F Fresnet, G Baravian, S Pasquier, C Postel, V Puech, A Rousseau and M Rozoy
- 1323 On the plasma parameters of a planar inductive oxygen discharge  
J T Gudmundsson, A M Marakhtanov, K K Patel, V P Gopinath and M A Lieberman
- 1332 RF discharge modelling in a N<sub>2</sub>O/SiH<sub>4</sub> mixture for SiO<sub>2</sub> deposition and comparison with experiment  
K Radouane, L Date, M Yousfi, B Despax and H Caquineau

(Continued on inside back cover)